

Systematic QA procedures for silicon micro-strip sensors used in CBM

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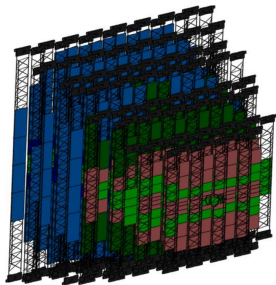
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*Workshop on Perspectives for Joint Science
and Academic Training at FAIR and NICA*

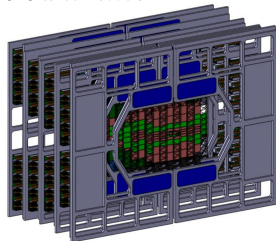
November 16, 2016

Introduction

Silicon Tracking System of CBM



STS carbon ladders

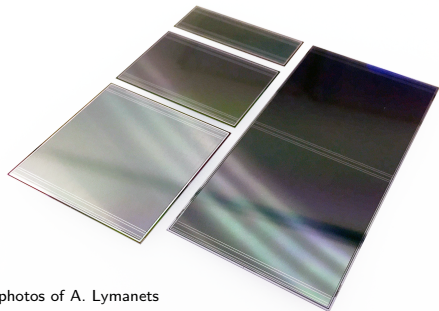


STS units (drawings of O. Vasylyev)

- Core tracking detector of CBM
 - ▶ momentum resolution $\Delta p/p \simeq 1.5\%$
 - ▶ hit efficiency $\gtrsim 95\%$
- Technical challenges:
 - ▶ ultra low material budget ($\simeq 8\% X_0$)
 - ★ electronics outside of acceptance
 - ★ connected to sensors with microcables
 - ★ double-sided sensors
 - ▶ occupancy up to 10 MHz/cm^2
 - ▶ self-triggering electronics
 - ▶ hundreds of sensors to be checked:
 - ★ QA procedures are required
- Operational conditions:
 - ▶ $1 \text{ T} \times \text{m}$ magnetic field
 - ▶ constant temperature of -5°C maintained

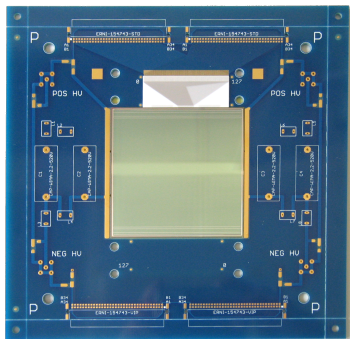
Silicon micro-strip sensors

- Sensor characteristics:
 - ▶ n-type silicon
 - ▶ double sided, 7.5° strip inclination angle on p-side
 - ▶ $300\ \mu\text{m}$ thick, $58\ \mu\text{m}$ pitch
 - ▶ required radiation hardness $2 \times 10^{14}\ 1\ \text{MeV}\ n_{\text{eq}}/\text{cm}^2$
- Two vendors: CiS, Hamamatsu



photos of A. Lymanets

$6.2 \times 6.2\ \text{cm}^2$ microstrip sensor
inside the supporting PCB frame

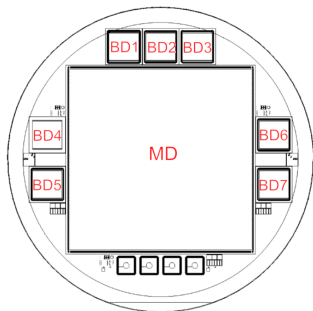


- Various sizes ($\simeq 1000$ in total):
 - ▶ $2.2 \times 6.2\ \text{cm}^2$ (tens)
 - ▶ $4.2 \times 6.2\ \text{cm}^2$ ($\simeq 300$)
 - ▶ $6.2 \times 6.2\ \text{cm}^2$ ($\simeq 300$)
 - ▶ $12.4 \times 6.2\ \text{cm}^2$ ($\simeq 300$)

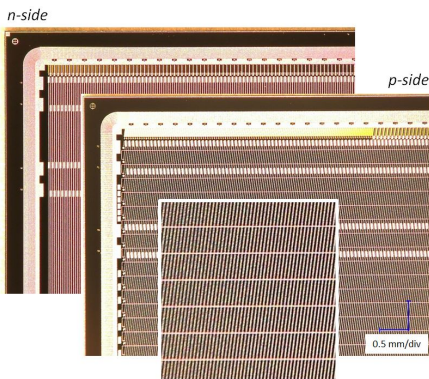
Quality assurance by vendors

- Production procedure (and QA)

- 1 wafer etching
- 2 electrical tests ($< 400\text{ V CiS}$, $< 200\text{ V Hamamatsu}$)
 - ★ current-voltage (IV), capacitance-voltage (CV), pin-holes, bad strips...
- 3 dicing (laser, diamond)
- 4 electrical tests (CiS, optional)



CiS wafer layout for $6.2 \times 6.2\text{ cm}^2$ sensors



corner view of CiS sensors

- More QA performed by vendors:
 - ▶ **contra:** it costs money
 - ▶ **pro:** it saves our manpower
- Though cross-check is required (can be $\simeq 10\%$)

QA scheme

Pre-production stage: 100% of sensors tested at Quality Assurance Centers

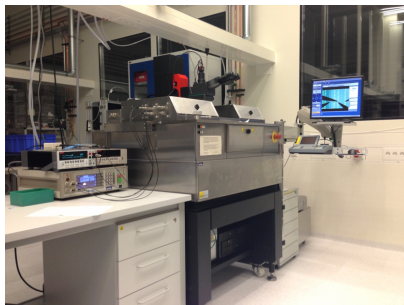
Production stage: 5–10% + suspicious sensors from optical inspection to be tested

- 1% of sensors to be characterised in-depth (verify QA by vendors)
- QA centres:
 - ▶ GSI, Darmstadt
 - ★ electrical tests
 - ★ tests with radiation source (sensor R&D, module tests)
 - ★ tests with infrared laser (sensor R&D, module test)
 - ▶ University of Tübingen
 - ★ electrical tests
 - ★ optical inspection
 - ▶ JINR, Dubna
 - ★ electrical tests

Butches of sensors to be split between centres during mass production

Electrical tests

GSI probe station



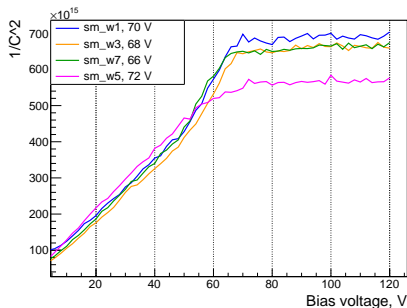
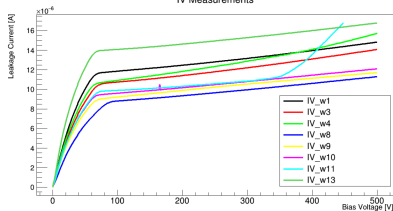
GSI probe station (customised by P. Larionov)

- Süss PA300PS probe station
 - ▶ 1 μm movement precision in X-Y-Z directions
 - ▶ chuck rotation option (covers $\pm 7.5^\circ$)
 - ▶ temperature and humidity control
 - ▶ needles with 5 μm tips
- Keithley 2410 SourceMeter
 - $V < \pm 1100 \text{ V}$, $\Delta I = 10 \text{ pA}$
- Keithley 6487
 - picoammeter/voltage source,
 $I = 2 \text{ nA} - 20 \text{ mA}$, $V = 505 \text{ V}$
- QuadTech 7600 precision LCR-meter
 - $V_{\text{bias}} = 500 \text{ V}$,
 - $f = (10^{-4} - 2) \text{ MHz}$,
 - 0.05% accuracy
- Keithley 708B 8×12 switching matrix (up to 1100 V)
- LabView based software:
 - ▶ pinhole
 - ▶ strip current
 - ▶ coupling capacitance

Electrical tests

examples of IV and CV curves from GSI

IV Measurements



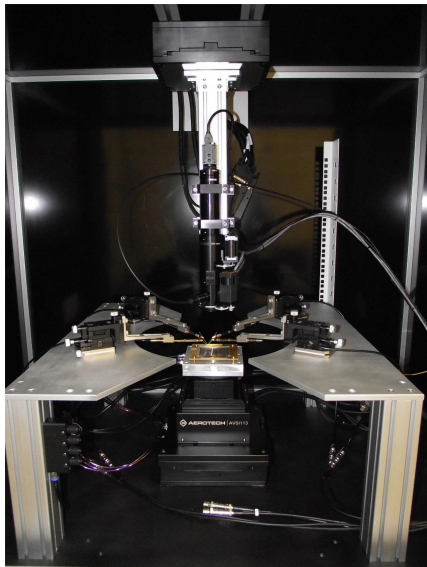
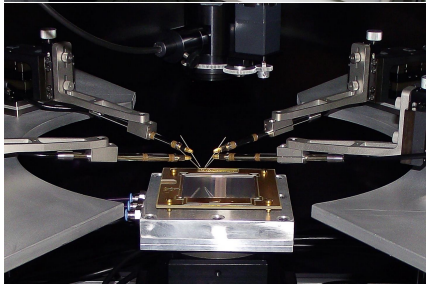
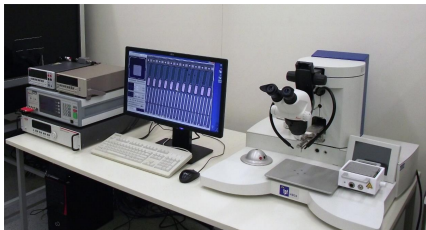
- IV tests of C6 generation, batch 350191
 - ▶ kink indicates full depletion
 - ▶ cyan line shows break down
 - ▶ noise proportional to dark current
- CV tests of CiS sensors
 - ▶ saturation of $1/C^2$ indicates full depletion
 - ▶ charge collection inversely proportional to the bulk capacitance
- Validation of tests of vendors
- signal $\sim 1/C$, noise $\sim I$

Electrical tests

in Tübingen University

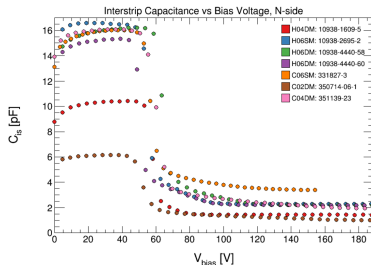
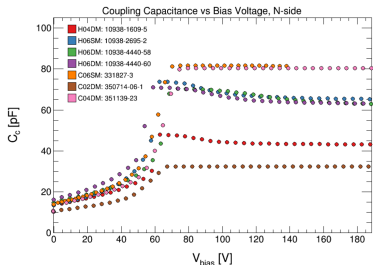
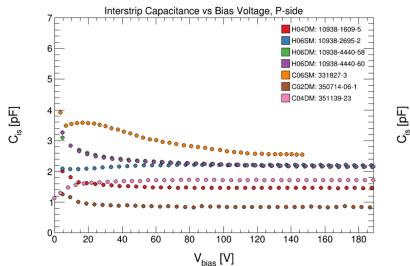
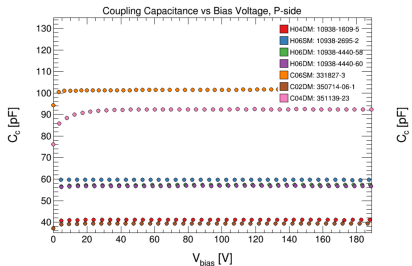
Custom made prob station:

photos of Ia. Panasenko



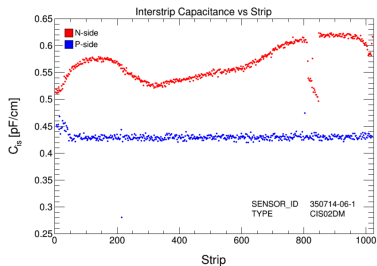
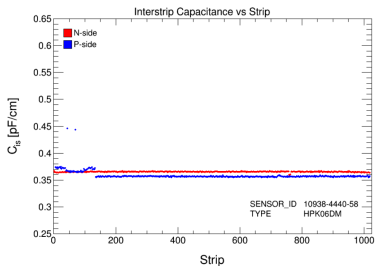
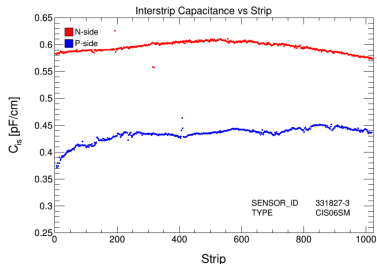
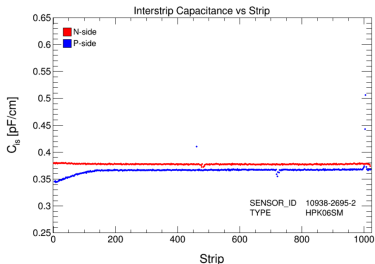
Individual strip tests in Tübingen University

interstrip capacitance vs bias voltage



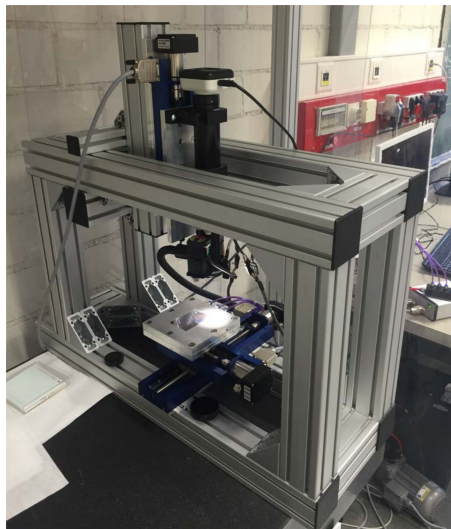
Individual strip tests in Tübingen University

interstrip capacitance per strip



Optical inspection setup

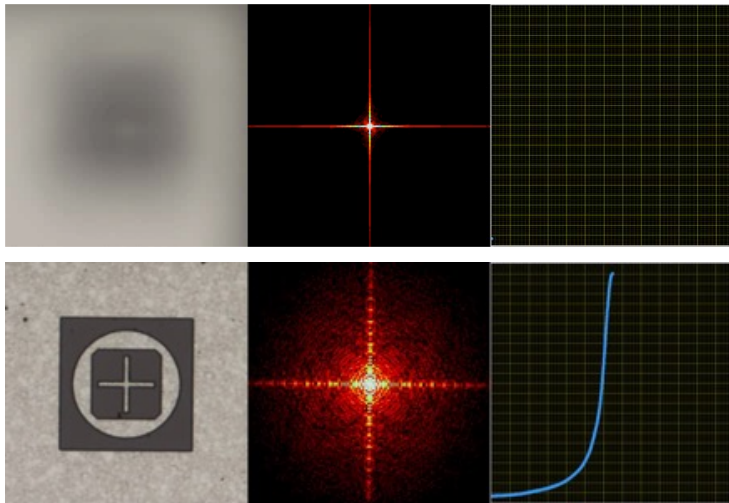
- Flexible design
 - ▶ inspection of different objects (different sensor size/types)
 - ▶ micro-cable inspection
- Low hardware dependence, adaptable to almost any hardware
- Configurable QA procedures as plugins
- Report building, storage, viewing and manipulations
- Constant improvement of performance
 - ▶ inspection times 1 hour → 4 min per sensor side



Optical inspection

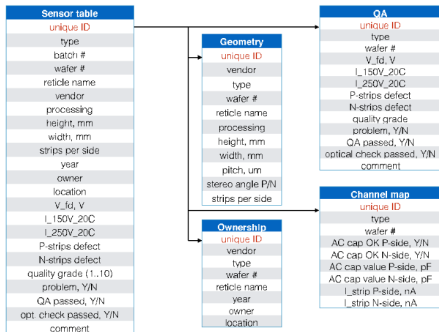
auto-focusing

Source image at different focus values, Fourier transformed image and total amplitude of transformed image ($\simeq 1/3 \mu\text{m}$ focusing precision):



Database

- Reports formed during analysis to be stored in Database
- Centralised data storage for CBM–FairDB
- 1 full inspection is 12.2 GB per 6×6 sensor (n and p sides)
- Up to 40 TB of images needs to be stored → tape storage gStore at GSI
- Database interfaces are currently being developed



Conclusions

- Three Quality Assurance centres: GSI, Tübingen Univ., JINR
- Quality Assurance procedures to be developed before mass production of sensors
- Cross-check of information, provided by vendors
 - ▶ all sensors undergo optical inspection
 - ▶ suspicious items and random 1/10 undergo electrical tests
- Though electrical tests may be harmful: optical inspection preferable
- Database development is in progress
 - ▶ QA data to be stored and then easily accessed
- Currently, QA setups helps to perform sensor R&D

Back-up slides

Parameters measured by CiS

The following parameters are checked during quality assurance at CiS:

- current-voltage (IV) and capacitance-voltage ($1/C^2$ vs. V) curve IV up to 250 V, if possible up to 400 V: while still on wafer and also after dicing.
- Check for depletion voltage $U_{depl} < 90$ V.
- Check for leakage current $I_{leak} < 50\mu A$ at $U_{depl} = +10V$
- Bulk resistivity (R measurement)
- Strip test, on all strips (p and n sides, pin-holes, shorts to neighbors, interrupts), at 20 V
- Check for leakage current per strip $< 2nA$ (a typical normal performance value),
- On a few strips: strip isolation
- Random sample of Poly-Si resistors ($R = 1$ M Ω)
- A detailed documentation of the test data is supplied.

Parameters measured by Hamamatsu

At Hamamatsu, the following parameters are checked:

- current-voltage (IV) and capacitance-voltage (CV) curve, up to 200V
- estimation of the full-depletion voltage
- strip test: all strips (p and n sides, including the corner strips; AC aluminum open, AC aluminum short), at 30 V.
- the double-metal routing lines cannot be tested directly but a fault may show up as an abnormal value of the strip's capacitance.
- check of one sensor per batch for the value of the polysilicon resistor pattern, on p and n-sides; determination of minimum and maximum and average value.

Finally:

- The sensors are shipped diced (“stealth dicing”, i.e. using a laser) and packaged in clean room paper envelopes that are tightly arranged in a box.
- A detailed documentation of the test data is supplied.

How to measure

